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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/500,543	12/20/2004	Jorg Schottek	LU 6001 (US)	6726
34872 Basell USA Inc	7590 05/09/200	EXAMINER		
Delaware Corporate Center II			LEE, RIP A	
2 Righter Parkway, Suite #300 Wilmington, DE 19803			ART UNIT	PAPER NUMBER
			1796	
			MAIL DATE	DELIVERY MODE
			05/09/2008	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)		
	10/500,543	SCHOTTEK ET AL.		
Office Action Summary	Examiner	Art Unit		
	RIP A. LEE	1796		
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	orrespondence address		
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING D. - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be time will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).		
Status				
1) ☐ Responsive to communication(s) filed on <u>February</u> 2a) ☐ This action is FINAL . 2b) ☐ This action is application is in condition for allowed closed in accordance with the practice under Expression in the practice of the p	s action is non-final. nce except for formal matters, pro			
Disposition of Claims				
4) ☐ Claim(s) 3-6 and 9-11 is/are pending in the ap 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 3-6 and 9-11 is/are rejected. 7) ☐ Claim(s) 3, 4, 9 and 10 is/are objected to. 8) ☐ Claim(s) are subject to restriction and/o Application Papers 9) ☐ The specification is objected to by the Examine 10) ☐ The drawing(s) filed on is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to by the examine and is/are: a) ☐ according to the above claim(s) are subjected to is/are: a) ☐ according to the above claim(s) is/are: a) ☐ according to the above claim(s) is/are: a) ☐ according to the above claim(s) is/are: a)	wn from consideration. or election requirement. or.	Examiner.		
Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	tion is required if the drawing(s) is obj	ected to. See 37 CFR 1.121(d).		
Priority under 35 U.S.C. § 119				
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 				
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date <u>02-28-2008</u> .	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate		

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DETAILED ACTION

This office action follows a request for continued examination (RCE) under 37 § C.F.R. 1.114, filed on February 28, 2008. Claims 3-6 and 9-11 are pending.

Claim Objections

1. Claims 3, 4, 9, and 10 are objected to because of the following informalities: In the description of D, please delete the term "ligand." That is, D is simply an uncharged Lewis base. Appropriate corrections are required.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:
 - 1. Determining the scope and contents of the prior art.
 - 2. Ascertaining the differences between the prior art and the claims at issue.
 - 3. Resolving the level of ordinary skill in the pertinent art.
 - 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

4. Claims 3-6 and 9-11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Resconi *et al.* (U.S. 6,191,294).

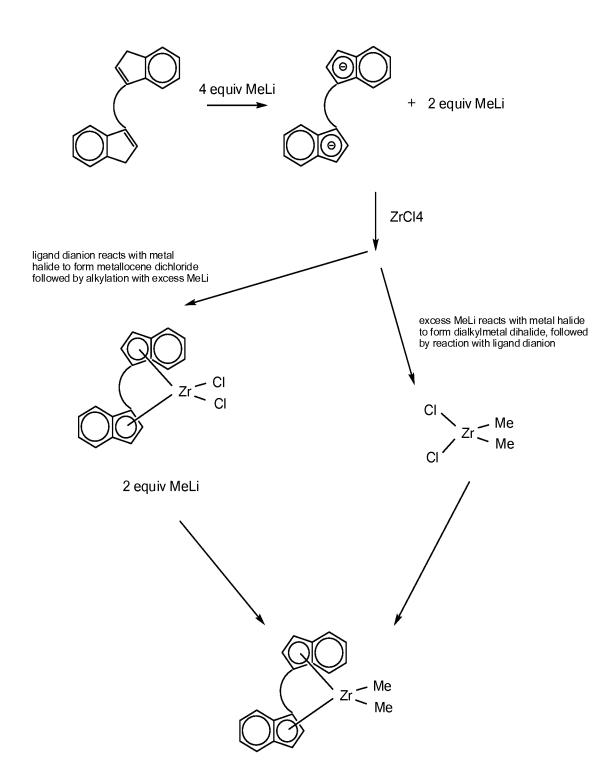
A process for the racemoselective preparation of silicon-bridged dialkyl ansametallocenes of formula (I) which comprises contacting a starting ligand compound of formula (II) with a transition metal dialkyl compound of formula (III) wherein the transition metal dialkyl compound of formula (III) is produced above -30 °C by combining a compound M^1X_{x+2} with from 2 to 2.5 equivalents of a compound R^1M^3 in the presence of a ligand compound D.

Resconi *et al.* (U.S. 6,191,294) teaches a general synthesis for a series of metallocene dialkyl complexes. The compound Me₂Si(2-MeInd)₂MMe₂ is described in col. 5, line 26, and it would be obvious to apply the general synthetic procedure to make this specific compound. Example 1 of the patent discloses treatment of neutral ligand with four equivalents of MeLi in Et₂O at -20 °C. The resulting solution is cooled to -80 °C and then added to ZrCl₄/pentane slurry, also maintained at -80 °C. The reaction mixture is then allowed to warm to room temperature. In this reaction, Et₂O is considered the uncharged Lewis base D of formula (III) of the claim.

The reactions disclosed in the prior art are likely to proceed via two pathways, shown below; ring substituents omitted for clarity. It is clear that deprotonation of the ligand occurs in the first step. Subsequently, one reaction pathway (shown on the left) involves complexation to form metallocene dichloride, followed by alkylation with excess MeLi to form metallocene dialkyl. The second reaction pathway involves reaction of excess MeLi with ZrCl₄, with concomitant formation of Me₂ZrCl₂ (shown on the right). Reaction with ligand dianion results in the formation of the metallocene dialkyl.

The reaction pathway on the right is germane to the subject of the instant claims. In this case, formation of Me₂ZrCl₂ appears to takes place above -30 °C (as the reaction warms to room temperature). Although the reaction mechanism is not disclosed in the reference, a reasonable basis exists to believe that the reaction occurs by the path shown on the right, and since the PTO can not conduct experiments, the burden of proof is shifted to Applicant to establish any unobviouness differences. *In re Best*, 562 F.2d 1252, 1255, 195 USPQ 430, 433 (CCPA 1977). *In re Spada*, 911 F.2d 705, 709, 15 USPQ2d 1655, 1658 (Fed. Cir. 1990).

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5. Claims 3-6 and 9-11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Resconi *et al.* (WO 02/83699).

Resconi *et al.* (WO 02/83699) teaches a general synthesis for a series of metallocene dialkyl complexes. Example 3 of the patent discloses treatment of neutral ligand (indenyl) with four equvalents of MeLi in Et₂O at room temperature, resulting in the formation of Ind₂ZrMe₂. The dimethyl complex is then converted to its dichloride derivative in a subsequent step. The compound Me₂Si(2-MeInd)₂ZrCl₂ is described on page 8, line 15, and it would have been just as obvious to extend this synthesis for the preparation of Me₂Si(2-MeInd)₂ZrMe₂ in order to make Me₂Si(2-MeInd)₂ZrCl₂. As elucidated in the previous paragraph, the reaction of interest can proceed via the pathway shown on the right, and in this event, combination of ligand (II) with a transition metal dialkyl compound of formula (III) is carried out well above -30 °C. Although the reaction occurs by the path shown on the right, and since the PTO can not conduct experiments, the burden of proof is shifted to Applicant to establish any unobviouness differences. *In re Best*, 562 F.2d 1252, 1255, 195 USPQ 430, 433 (CCPA 1977). *In re Spada*, 911 F.2d 705, 709, 15 USPQ2d 1655, 1658 (Fed. Cir. 1990).

Applicant cannot rely upon the foreign priority papers to overcome this rejection because a translation of said papers has not been made of record in accordance with 37 CFR 1.55. See MPEP § 201.15.

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The prior art made of record but not relied upon is considered pertinent to the Applicant's

disclosure. The following references have been cited to show the state of the art with respect to

synthesis of metallocenes using the methodology presented in Resconi et al. (U.S. 6,191,294)

and Resconi et al. (WO 02/83699). The art represents obvious variations of the same reaction

sequence.

Resconi et al. WO 00/75151

Balboni et al., Inorg. Chem. 2001, 40, 6588-6597.

Resconi et al. Organometallics 2000, 19, 420-429.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Rip A. Lee whose telephone number is (571)272-1104. The

examiner can be reached on Monday through Friday from 9:00 AM - 5:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Vasu S. Jagannathan, can be reached at (571)272-1119. The fax phone number for

the organization where this application or proceeding is assigned is (571)273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on the access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll free).

/Rip A. Lee/

Primary Examiner, Art Unit 1796

May 5, 2008